

LAW OFFICES OF  
**JOHN S. MUNDAY**  
PATENTS, TRADEMARKS, COPYRIGHTS  
RELATED MATTERS OF LAW

P.O. BOX 423  
ISANTI  
MINNESOTA, 55040

TELEPHONE 763-444-8296  
FACSIMILE 763-444-8781  
E-MAIL mustpatent@aol.com

May 13, 2005

Mr. Scott Jacobs  
Archtek, Inc.  
12105 West Cedar Avenue  
Lakewood CO 80228

RE: CUSTOM DENTAL TRAY  
European Patent Application  
No. 96911788.6 EPO  
Our ref.: 96123.EP

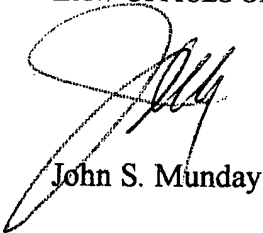
Dear Scott:

Enclosed is the Rule 51(4) EPC communication along with the application text and drawings that will be granted in the subject case. As you recall, I noted that you will need to select the specific countries that you want patent protection to be obtained. This also relates to the invoice I sent to you on February 25, 2005, which has not been paid.

As I previously noted, we can hold off on decisions until the last few days, to delay the expenses. Our first deadline is June 26, 2005, when we are to authorize the agent to proceed with the grant procedure.

Very truly yours,

LAW OFFICES OF JOHN S. MUNDAY



John S. Munday

reference that once the improper elimination of a Si-Ge alloy in favor of a Si doped wafer one skilled in the art would even consider adding boron to relieve stress at the p<sup>+</sup> layer.

There are three distinct systems under consideration here:

1. Prior art systems with heavy boron doped in silicon that has been found to be ineffective.
2. Wu, who uses lightly doped or non doped silicon alloys having germanium of at least 18% and preferably 30%. Radamson who also teaches Si-Ge alloys.
3. Applicants, who uses the prior art heavy doped boron in silicon with the addition of 1% germanium to achieve proper etching as noted in the specification.

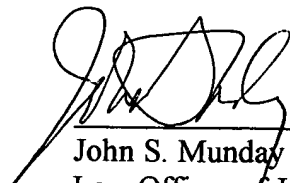
Reconsideration of the rejections and allowance of the claims is earnestly urged. The Examiner has objected to the claims as not reciting "no more than about 1%" Ge. Applicants made that amendment some time ago, in an amendment filed and entered on January, 2004. The critical nature of this limitation is that one obtains a strain compensated p<sup>+</sup> layer that functions as an etch stop. This is not disclosed or suggested anywhere in any of the art of record. The Examiner has also cited other references to show various devices recited in the other pending claims. A review of those references clearly shows that none of them remedy the deficiencies of the combination of Wu and Radamson as noted above.

It is respectfully requested that the Examiner consider the amendments and remarks herein, and pass this application to issue. If the Examiner considers this case ready for conclusion, other than by allowance, he is respectfully requested to call Applicant's attorney at the number listed below.

DATE: May 13, 2005

Respectfully submitted,  
Robert Horning et al.  
By their Attorney

Telephone:  
(763) 444-8296  
FAX  
(763) 444-8781

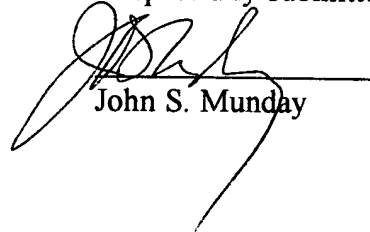
  
\_\_\_\_\_  
John S. Munday  
Law Offices of John S. Munday  
PO BOX 423  
Isanti, MN 55040

CERTIFICATE OF MAILING

I hereby certify that the attached correspondence is being deposited with the United States Postal Service and First Class Mail in an envelope addressed to: Mail Stop amendment non fee, Commissioner for Patents, PO Box 1450, Alexandria, VA 22313-1450, on the date appearing below.

DATE: May 13 2005

Respectfully submitted,

  
John S. Munday